

IN THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Canceled):
2. (Currently Amended): The process target as claimed in claim ~~[[1]]~~ 15, wherein the stoichiometric deficiency stems from ~~the composition of the intimate a blend of~~ formed by nickel oxide powders and nickel powders.
- 3-4. (Canceled).
5. (Currently Amended): The process target as claimed in claim ~~[[1]]~~ 15, wherein the nickel oxide is alloyed to a minority element.
6. (Currently Amended): The process target as claimed in claim 5, wherein the atomic percentage of the minority element is less than 50%, calculated with respect to the nickel.
7. (Currently Amended): The process target as claimed in claim 5, wherein the minority element is a material whose oxide is an electroactive material with anodic coloration.

8. (Currently Amended): The process ~~target~~ as claimed in claim 7, wherein the minority element is selected from the group consisting of Co, Ir, Ru, Rh, and mixtures thereof.

9. (Currently Amended): The process ~~target~~ as claimed in claim 5, wherein the minority element is a material whose oxide is an electroactive material with cathodic coloration.

10. (Currently Amended): The process ~~target~~ as claimed in claim 9, wherein the minority element is selected from the group consisting of Mo, W, Re, Sn, In, Bi, and a mixture of these elements.

11. (Currently Amended): The process ~~target~~ as claimed in claim 5, wherein the minority element is selected from the elements belonging to the column one of the Periodic Table.

12. (Currently Amended): The process ~~target~~ as claimed in claim 11, wherein the minority element is selected from the group consisting of H, Li, K, and Na.

13. (Currently Amended): The process ~~target~~ as claimed in claim 5, wherein the minority element is a metal or an alkaline earth or a semiconductor, the hydrated or hydroxylated oxide of which is protonically conductive.

14. (Currently Amended): The process target as claimed in claim 13, wherein the minority element is selected from the group consisting of Ta, Zn, Zr, Al, Si, Sb, U, Be, Mg, Ca, V, Y and ~~[[of]]~~ a mixture of these elements.

15. (Currently Amended): A process for manufacturing an electrochemical device comprising a thin layer based on nickel oxide, comprising producing a thin layer based on nickel oxide by magnetically enhanced sputtering using an essentially ceramic, spray-coated target comprising predominantly nickel oxide NiO<sub>x</sub>, wherein the nickel oxide is oxygen-deficient with respect to the stoichiometric composition NiO, wherein x is less than 1 and wherein the target has an electrical resistivity of less than 10 ohm.cm wherein it uses a ceramic target as claimed in claim 1.

16. (Canceled):

17. (Currently Amended): An electrochemical device prepared according to the process of claim 15, wherein the device comprises comprising at least one carrier substrate provided with a stack of functional layers, including said thin layer based on nickel oxide, at least one electrochemically active layer, capable of reversibly and simultaneously inserting ions, of the H<sup>+</sup>, Li<sup>+</sup> or OH<sup>-</sup> type, and electrons, ~~wherein said electrochemically active layer is based on nickel oxide obtained by the process as claimed in claim 15 and/or from the~~

~~essentially ceramic target.~~

18. (Currently Amended): An electrochemical device prepared according to the process of claim 15, wherein the device comprises ~~comprising~~ at least one carrier substrate provided with a stack of functional layers, including said thin layer based on nickel oxide, at ~~least one electrochemically active layer~~, capable of reversibly and simultaneously inserting ions, of the  $H^+$ ,  $Li^+$  or  $OH^-$  type, and electrons, wherein said nickel oxide is ~~electrochemically active layer is based on nickel oxide, said layer being~~ alloyed with a minority element consisting of a material whose oxide is an electroactive material with anodic coloration, ~~said layer being obtained from a target as claimed in claim 1.~~

19. (Canceled).

20. (Currently Amended): An electrochemical device prepared according to the process of claim 15, wherein the device comprises ~~comprising~~ at least one carrier substrate provided with a stack of functional layers, including said thin layer based on nickel oxide, at ~~least one electrochemically active layer~~, capable of reversibly and simultaneously inserting ions, of the  $H^+$ ,  $Li^+$  or  $OH^-$  type, and electrons, wherein said nickel oxide is ~~electrochemically~~ ~~active layer is based on nickel oxide, said layer being~~ alloyed with a minority element selected from the elements belonging to the column one of the Periodic Table, ~~said layer being obtained from a target as claimed in claim 1.~~

21. (Currently Amended): An electrochemical device prepared according to the process of claim 29, wherein the device comprises ~~comprising~~ at least one carrier substrate provided with a stack of functional layers, including said ~~at least one~~ electrochemically active layer, capable of reversibly and simultaneously inserting ions, of the  $H^+$ ,  $Li^+$  or  $OH^-$  type, and electrons, wherein said electrochemically active layer is a metal or an alkaline earth or a semiconductor, the hydrated or hydroxylated oxide of which is protonically conducted, ~~said layer being obtained from a target as claimed in claim 1.~~

22. (Canceled).

23. (Currently Amended): The process target as claimed in claim ~~[[1]]~~ 15, wherein the target has an electrical resistivity of less than 1 ohm.cm.

24. (Currently Amended): The process target as claimed in claim ~~[[1]]~~ 15, wherein the target has an electrical resistivity of less than 0.1 ohm.cm.

25. (Currently Amended): The process target as claimed in claim 5, wherein the atomic percentage of the minority element is less than 30%, calculated with respect to the nickel.

26. (Currently Amended): The process target as claimed in claim 5, wherein the atomic percentage of the minority element is less than 20%, calculated with respect to the nickel.

27. (Currently Amended): The process target as claimed in claim ~~[[1]]~~ 15, wherein nickel oxide powder is spray coated onto a metal substrate.

28. (Currently Amended): The process target as claimed in claim ~~[[1]]~~ 15, wherein nickel oxide and nickel are spray coated onto a metal substrate.

29. (New): A process for manufacturing an electrochemical device comprising an electrochemically active layer, comprising producing an electrochemically active layer by magnetically enhanced sputtering using an essentially ceramic, spray-coated target comprising predominantly nickel oxide  $\text{NiO}_x$ , wherein the nickel oxide is oxygen-deficient with respect to the stoichiometric composition  $\text{NiO}$ , wherein  $x$  is less than 1 and wherein the target has an electrical resistivity of less than 10 ohm.cm